



Karen Cinq-Mars

(Signature)

(Date)

<u>In Re Application of</u>	:	January 29, 2004
<u>Liebmann et al.</u>	:	
<u>Serial No. 10/707,962</u>	:	Examiner:
<u>Filed: 01-28-04</u>	:	IBM Corporation
<u>Title: ALTERNATING PHASE SHIFT MASK DESIGN FOR HIGH PERFORMANCE CIRCUITRY</u>	:	Dept. 18G/Bldg. 300-482 2070 Route 52 Hopewell Junction, New York 12533-6531

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed Form PTO-1449. Copies of the listed documents are also enclosed.

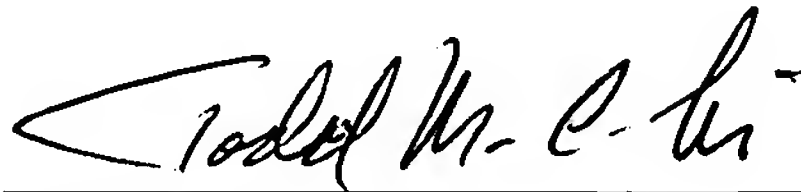
It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants undersigned attorney may be reached by telephone

FIS920030378US1

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,

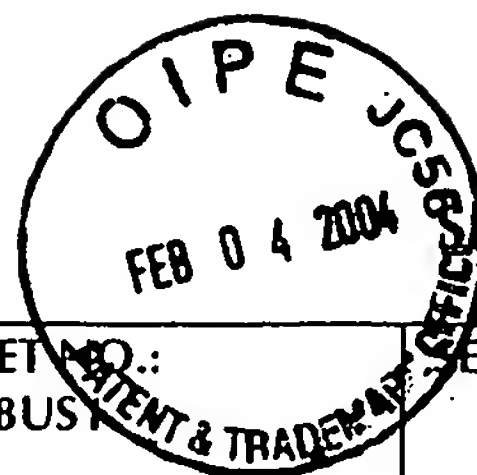


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TML/kcm

SUPPLEMENTAL INFORMATION DISCLOSURE

Sheet 1 of 1

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO.: FIS920030378USPTO	SERIAL NO.: 10/707,962
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: Lars Liebmann et al.	
(Use several sheets if necessary) (37 CFR 1.98(b))		FILING DATE: 01-28-04	GROUP:

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
	AT						
	AU						
	AV						
	AW						
	AX						
	AY						
	AZ						

		U.S. PATENT APPLICATION NO.	PUBLICATION DATE	INVENTOR			
	BA						
	BB						
	BC						
	BD						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB- CLASS	TRANSLATION YES	NO
	BE							
	BF							
	BG							
	BH							
	BI							

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

	BJ	Lithography, Resolution Enhancement, Design for Manufacturability; L. Liebmann, IBM Microelectronics, Semiconductor Research and Development Center, 13 pages
	BK	Exposing the DUV SCAAM – 75nm Imaging on the Cheap!; M. D. Levenson, T. Ebihara, SPIE Vol. 4692 (2002) pages 288-297.
	BL	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.